

# TOWARD ULTRA LOW POWER SPINTRONICS DEVICES

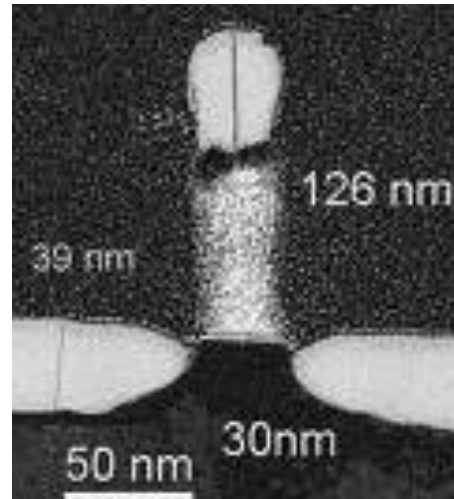
D.RAVELOSONA

- Institut d'Electronique Fondamentale
- UMR Thales CNRS (M.Bibes)
- CEA-SPEC (M.Viret)
- Ecole Polytechnique (P.Allongue)
- Laboratoire de Physique des solide(A.Thiaville)
- Ecole Centrale Paris (B.Dkhil)
- Laboratoire photonique et Nanostructures (A.Lemaitre)

# Nanoelectronics Vision for the Next Ten Years

*From how do we make devices smaller to how do we reduce power*

**MOSFET devices : significant increase in performance (node 20 nm)  
..... but Leakage power consumption increases at an exponential rate**



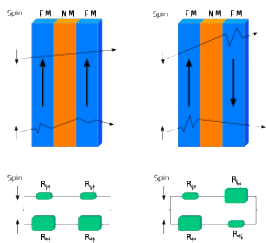
*Demonstrate new low power concepts for calculation,  
data storage, sensors.....*

# Nanoelectronics Vision for the Next Ten Years

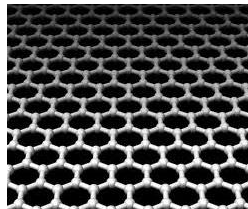
*From how do we make devices smaller to how do we reduce power*

## Emerging nanodevices

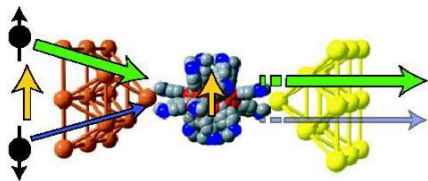
New functionalities on the nanometer scale



Spin Electronics



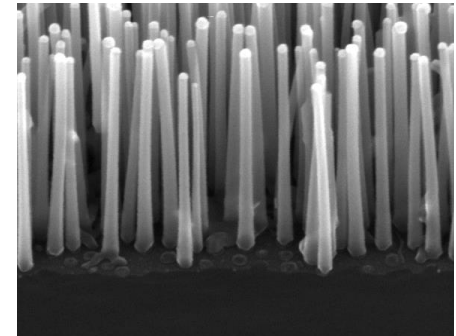
Carbon based electronics



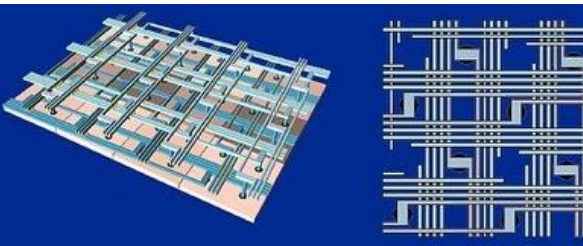
Molecular Electronics

## Energy harvesting

Photovoltaics/thermoelectricity based on new nano-objects



Nanomaterials



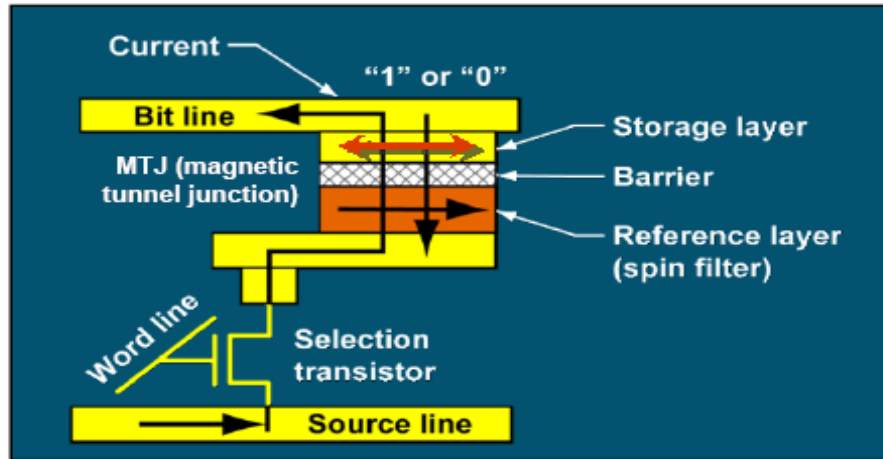
Hybrid CMOS circuits`  
Neuromorphic circuits

**Emerging architectures**  
Circuits based on emerging nanodevices  
New paradigm for calculation

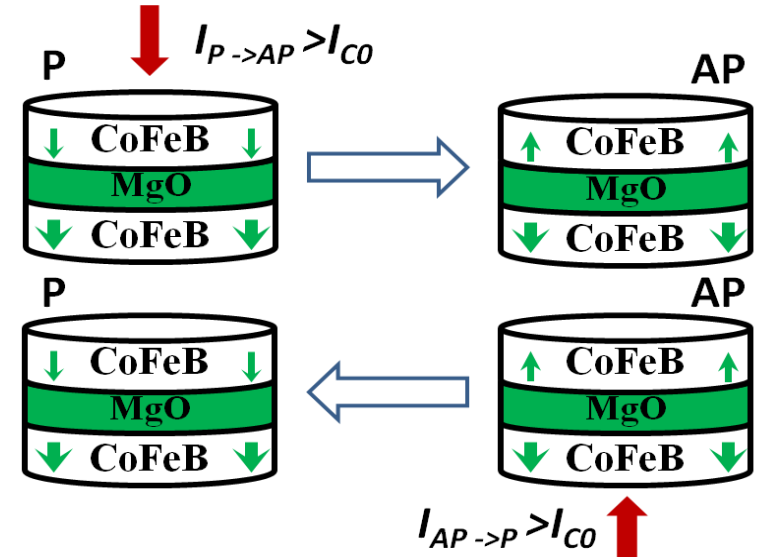
# Spintronics : a new route to reduce power

*Non volatile, highly scalable, high speed, unlimited endurance, high density*

**Spin Transfer Torque-RAM : use of a polarized current to switch magnetization**



$R_{MTJ} = 20 \text{ k}\Omega$ ,  $F = 40 \text{ nm}$ ,  $j_c = 10^6 \text{ A/cm}^2$   
 Switching time 10 ns,  $I_{WR} \sim 20 \mu\text{A}$



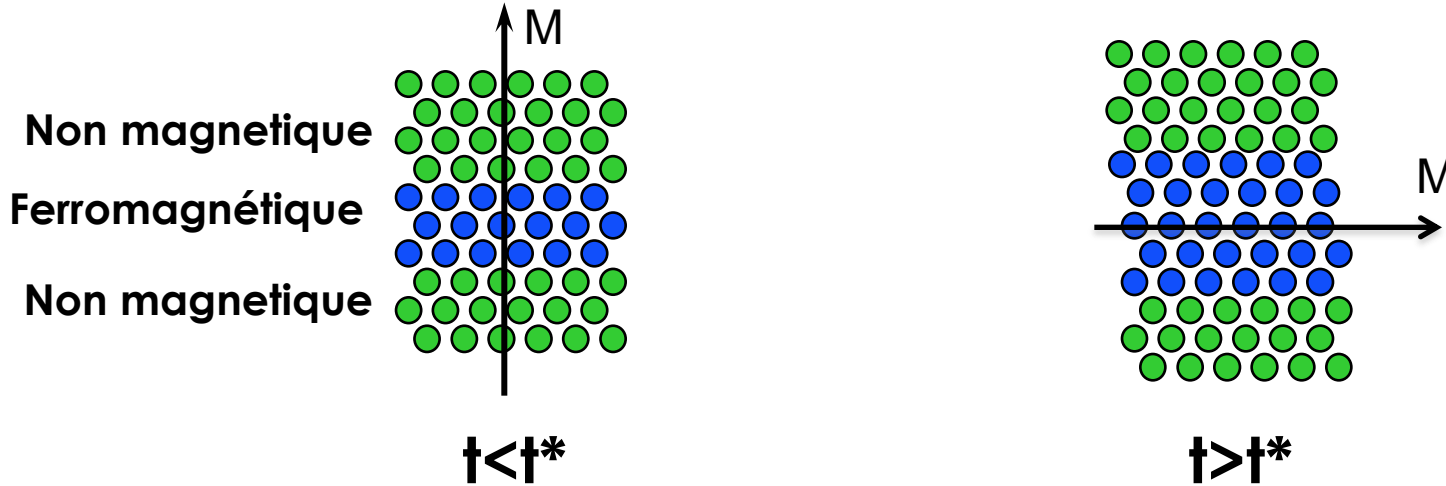
**MgO Tunnel junction : TMR > 200 %**

**Energy  $E_D$  dissipated in the switching process**  $E_D = RI^2 \times t_{\text{switching}}$

- Spin Transfer Torque RAM :  $E_D \sim 10^6 - 10^7 \text{ kT} \rightarrow 0.01 - 0.1 \text{ pJ}$ , no passive dissipation
- Transistor :  $E_D \sim 10^7 - 10^8 \text{ kT} \rightarrow 0.1 - 1 \text{ pJ}$

# Interface anisotropy

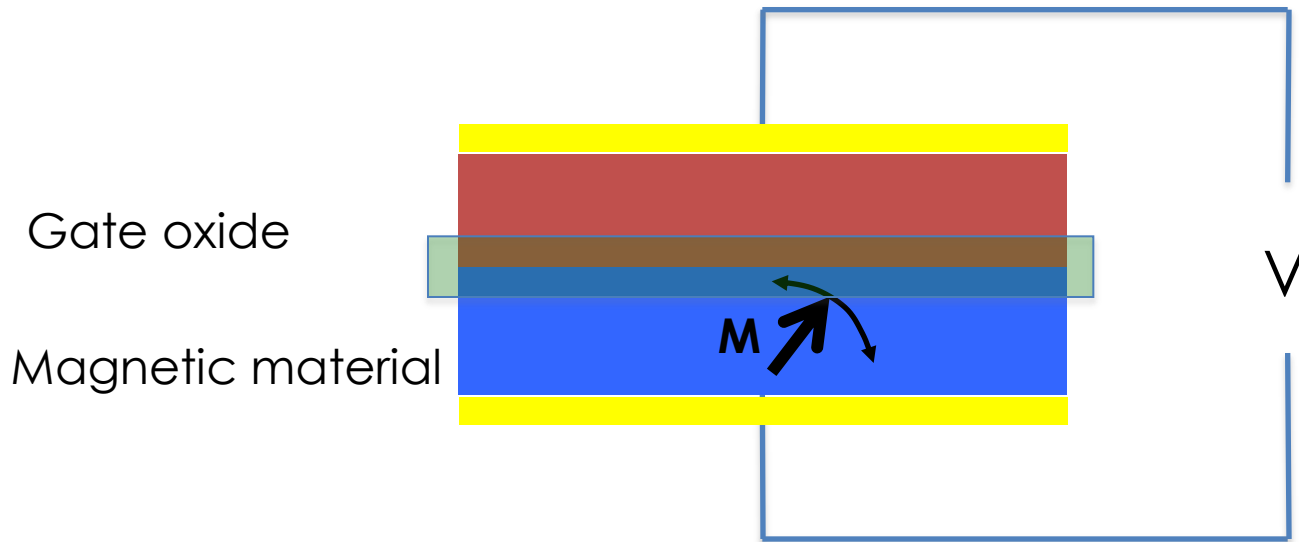
Magnetic properties are related to atomic short range order



- Important role played by the interfaces : presence of interface anisotropy for thickness  $t < t^*$
- NRJ barrier  $E_a \sim KV$  where  $V$  is the magnetic volume and  $K$  the anisotropy
- Enough thermal stability for data retention (NRJ barrier  $E_a > 50 \text{ kT}$  for 10 years)
- Writing current  $I_c \sim E_a$

Can magnetic properties at interfaces be modulated ?

# Electric field effect in hybrid Metal/Oxide/Ferromagnetic structures

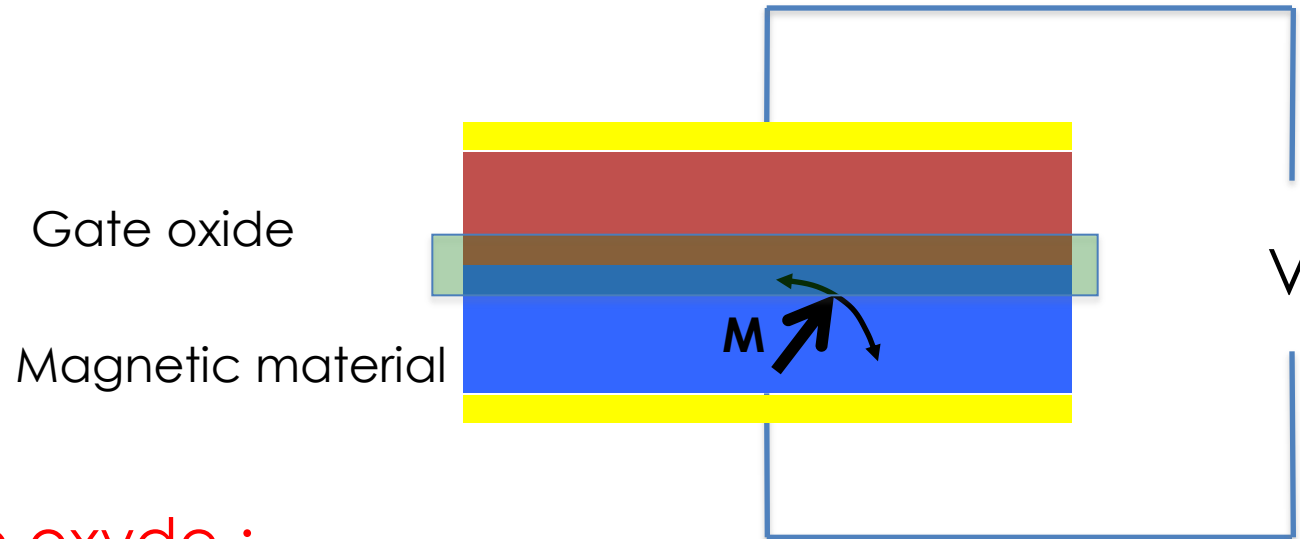


$$E_{\text{dissipated}} = \Delta Q \times \Delta V = C V^2$$

$\Delta Q$  : Amount of charges injected or extracted  
 $\Delta V$  : gradient of potential

- Voltage driven interface effect
- Dissipation << FemtoJoule

# Strategy



## Gate oxide :

- Dielectric : Charge effect
- Piezoelectric : Strain effect

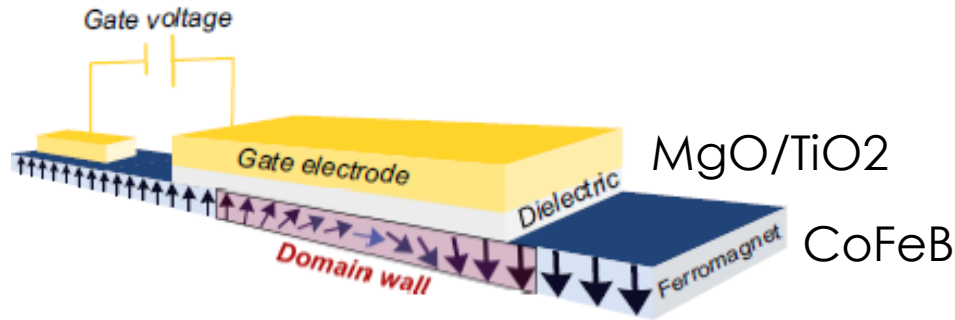
## Magnetic Materials :

- Metal
- Semiconductors

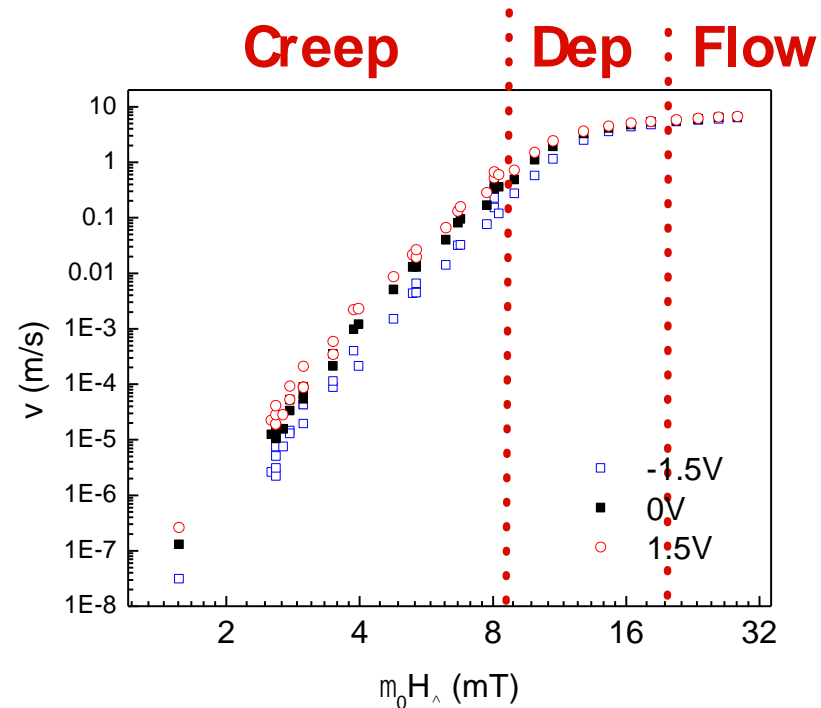
# Charge modulation in metals



## Domain wall propagation under electric field



$H = 2.6 \text{ mT}$

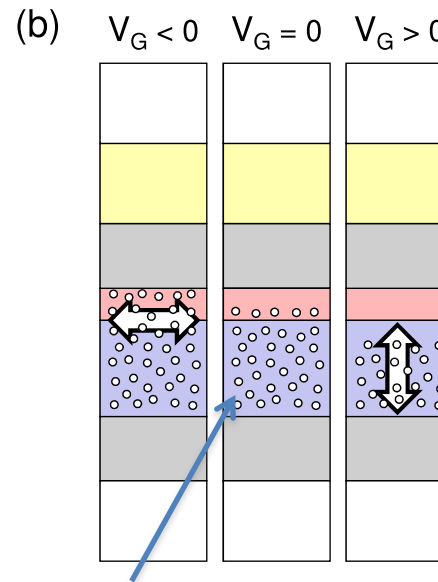
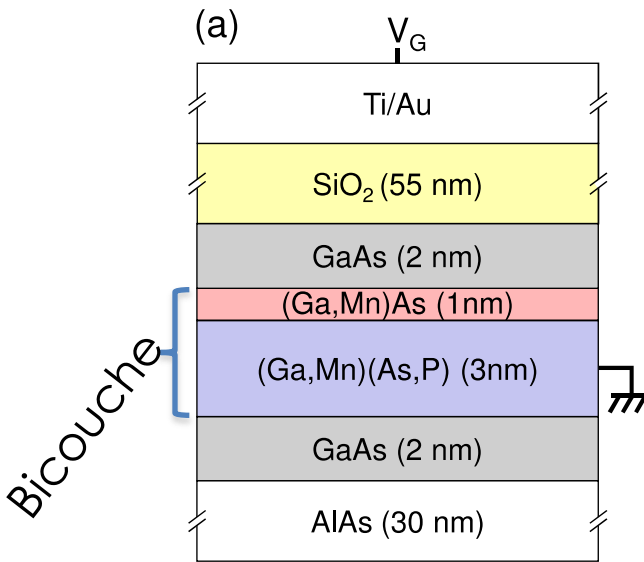


Electric field effect to assist domain wall propagation through anisotropy change (change of 1 mT under 1 V)

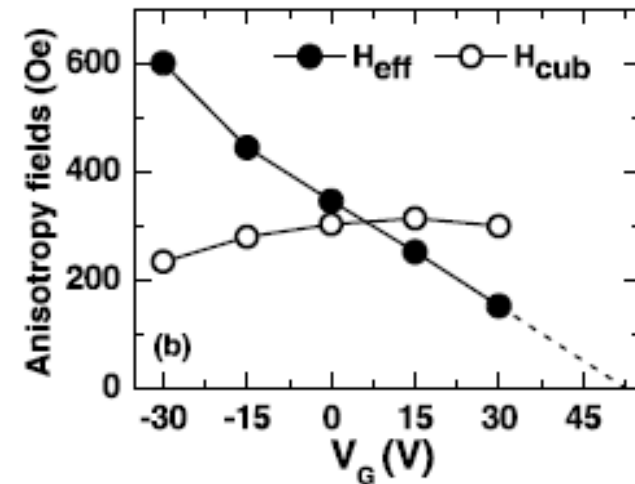
W.Lin et al, submitted PRL 2014



## Modulation of perpendicular anisotropy in bilayers (GaMnAsP)/(GaMnAs)



o : porteurs

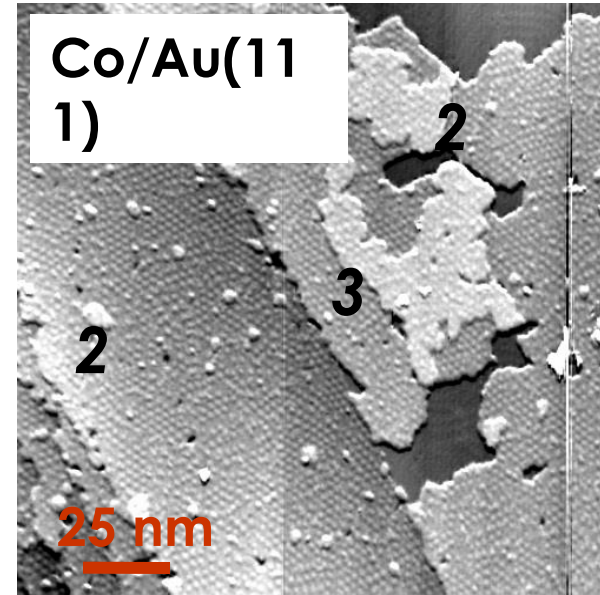
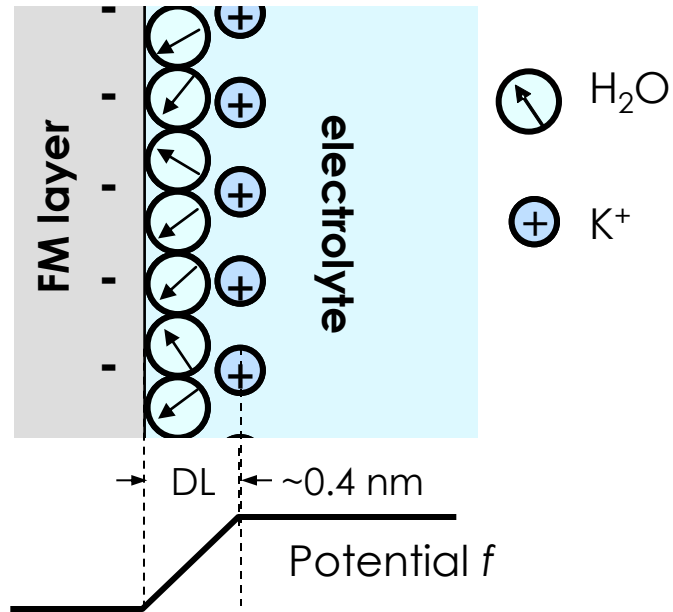


➤ Depending on the sign of  $V_G$ , either in-plane or out of plane anisotropy is favored

Niazi et al, APL 2013

# Magnetoelectirc effect using an electrochemical approach

## Modulation of perpendicular anisotropy in Au(111)/Co



### Solid/electrolyte contact:

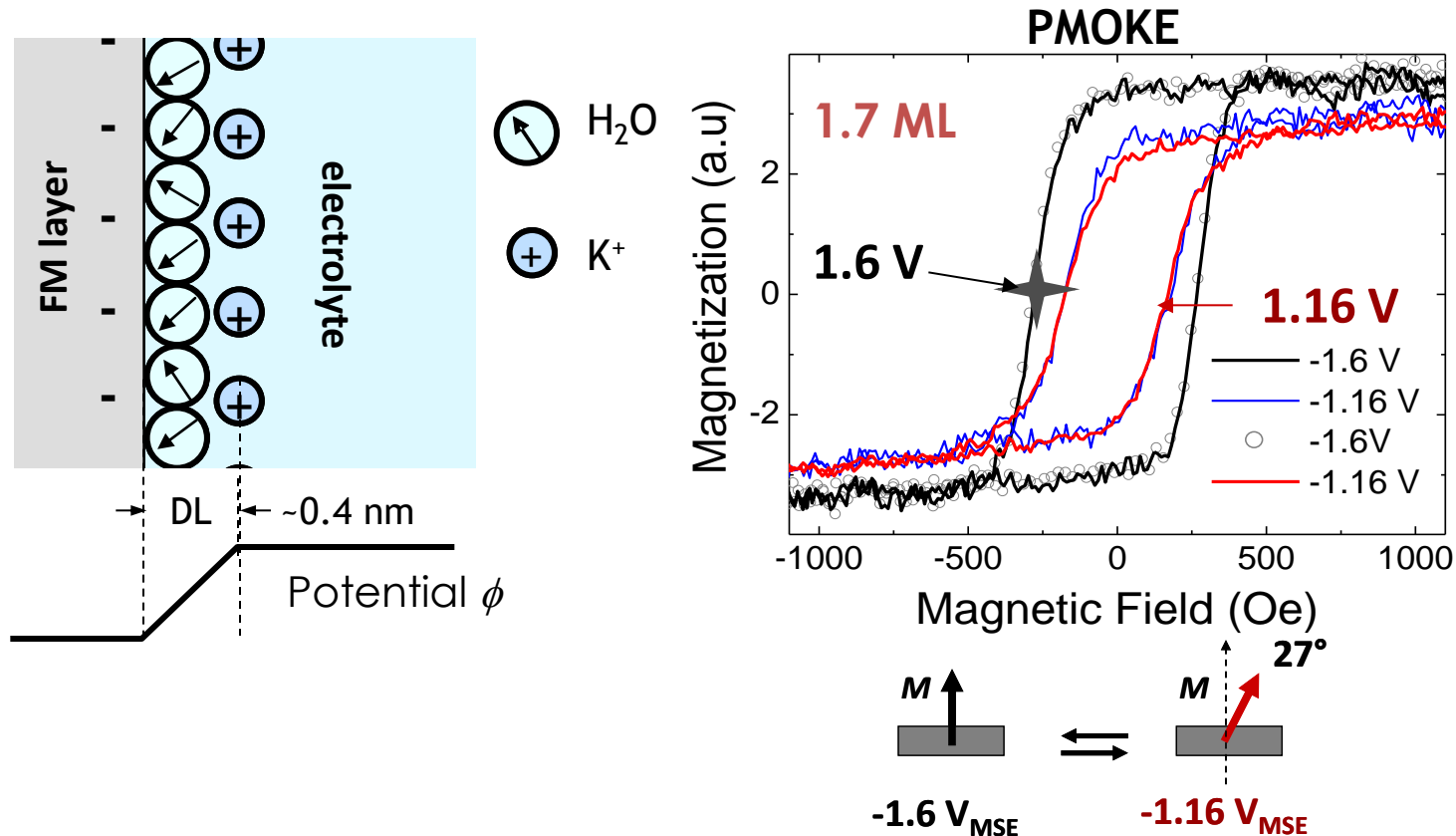
- **No need of a dielectric layer.**
- **E-field uniform and large (ca. 1 V/nm)**
- **No defects**

### In situ Electrodeposition :

- Epitaxial layers
- **Sample kept under potential control**
- **No oxide**

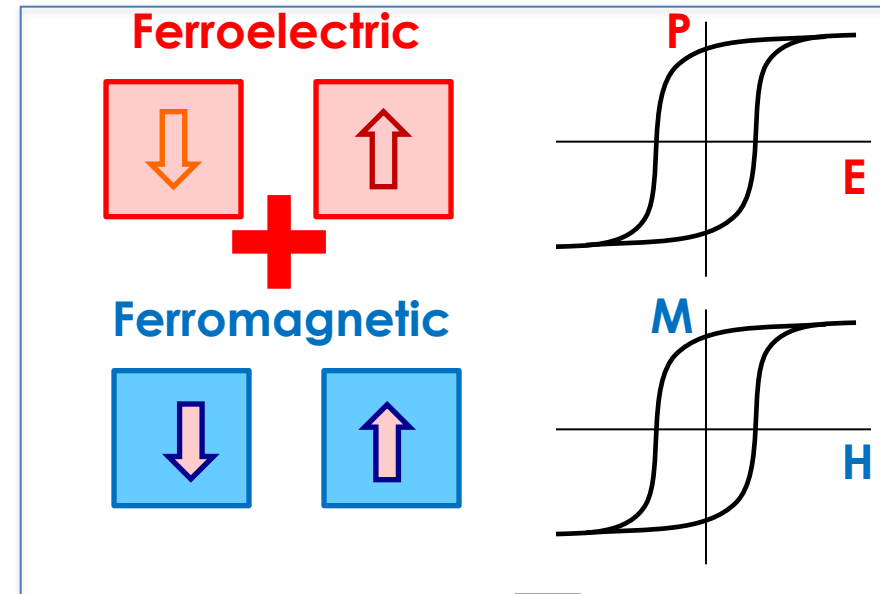
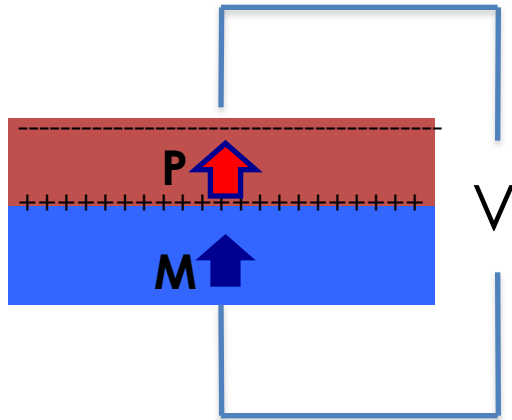
Tournerie et al, Phys. Rev. B 86 (2012) 104434

# Magnetoelectric effect using an electrochemical approach

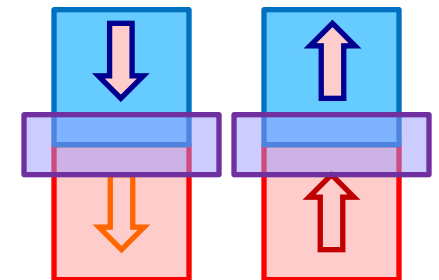


- Voltage effect in out of plane magnetized H-Co/Au(111):  
Linear (E-field effect), pure surface phenomenon, large ( $\Delta K_s/\Delta U = -130 \mu\text{J}/\text{m}^2/\text{V}$ )
- Voltage effect (sign + amplitude) depends on adsorbate on Co/Au(111)

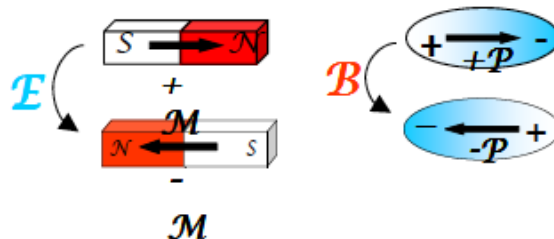
# Ferromagnetic/Ferroelectric structures



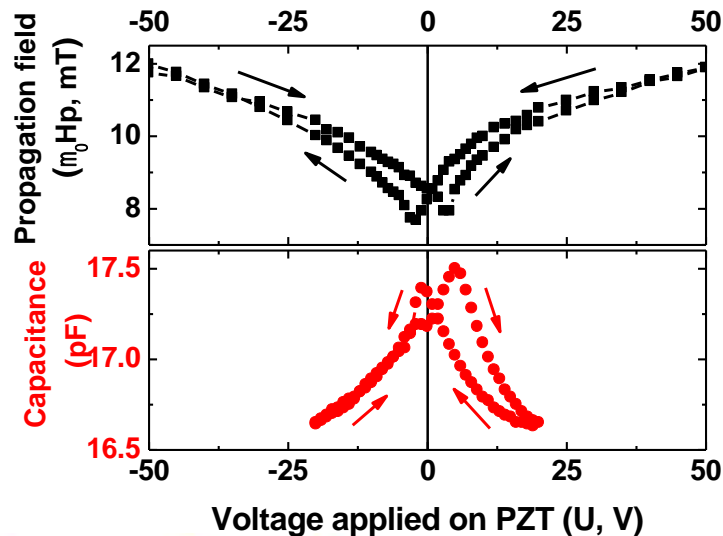
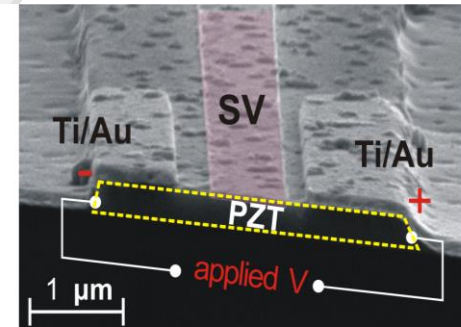
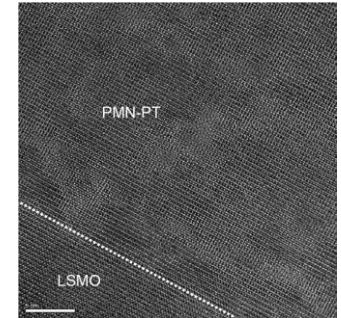
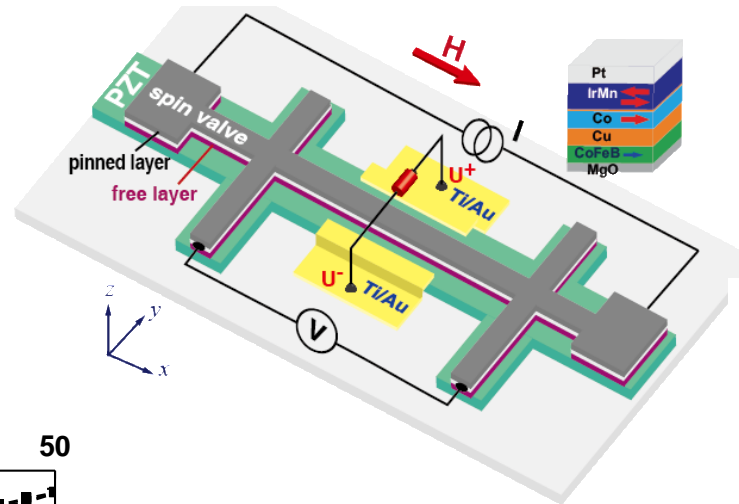
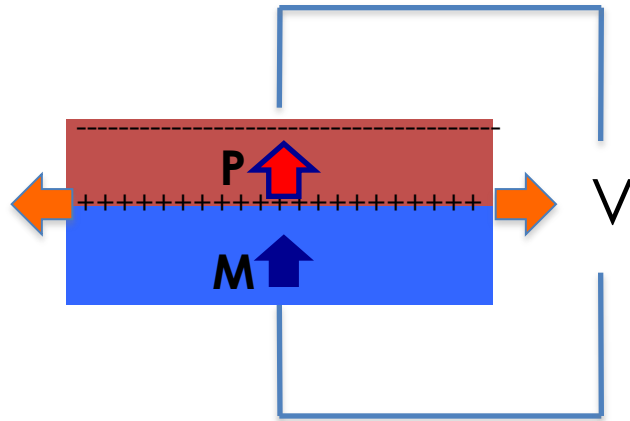
**Magnetoelectric Coupling at interfaces**



- Electric control of magnetization
- Magnetic control of polarization
- Induced magnetism in the ferroelectric
- New states at ferroelectric/ferromagnetic interfaces



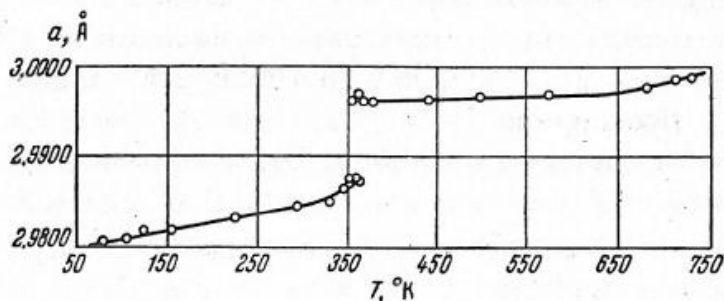
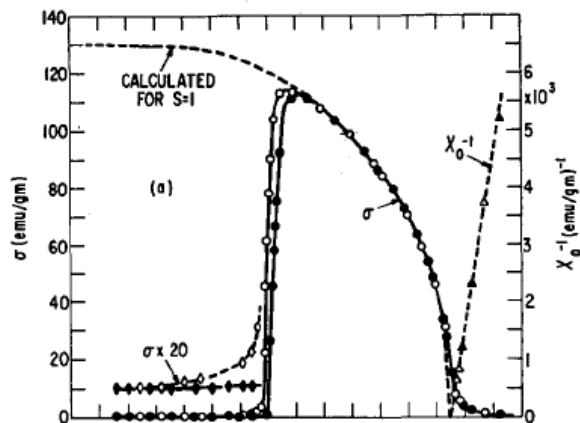
## All electrical integrated Ferromagnetic/Piezoelectric nanodevices



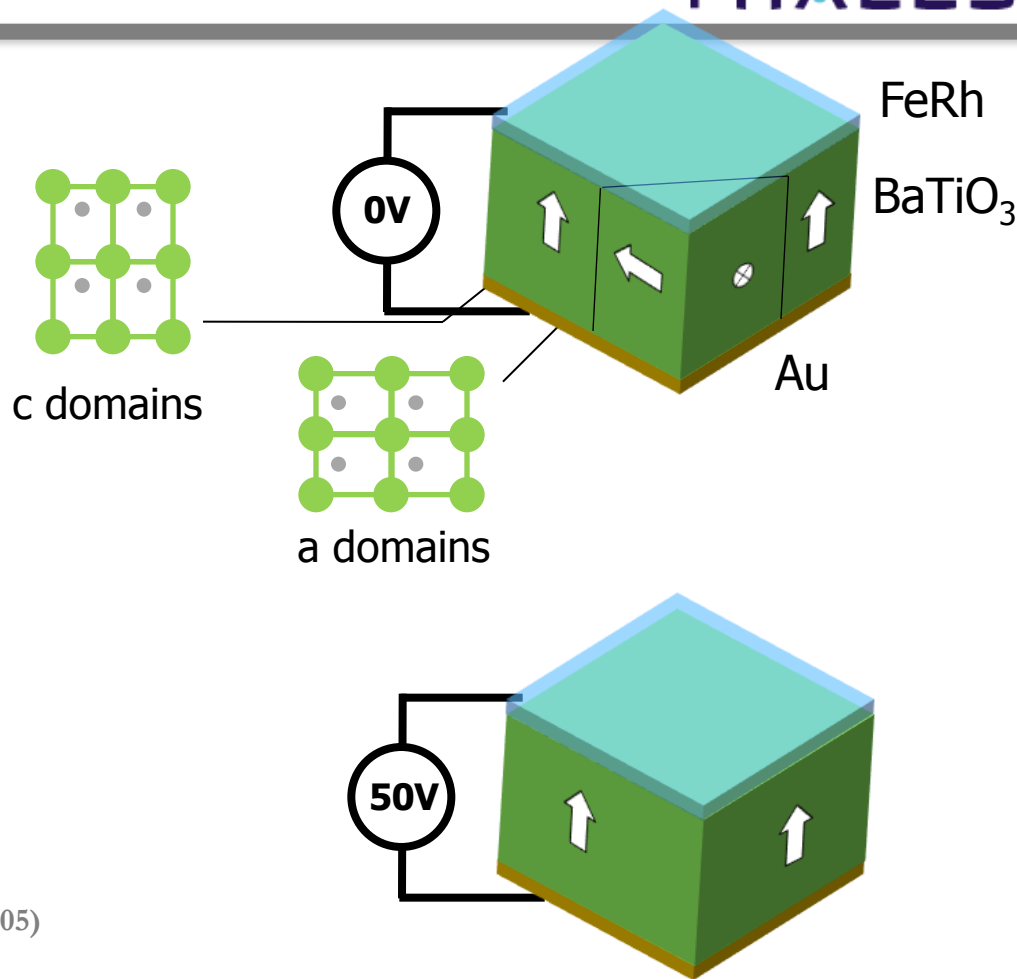
- 80% variation of  $H_c$  in an integrated nanodevice
- Demonstration of a domain wall gate under electric field

Lei et al, *Nature Materials* 2013

**FeRh alloys** : near 50/50 composition,  
transition from **AF to FM** at  $T^* \approx 370$  K



Kouvel et al, JAP 33, 1343 (1962) ; Maat et al, PRB 72, 214432 (2005)

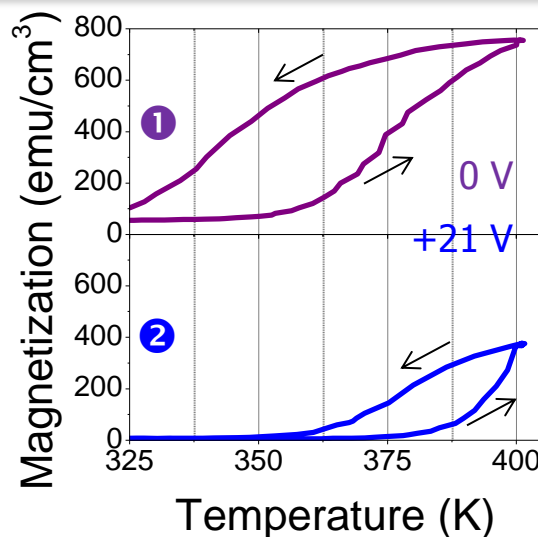
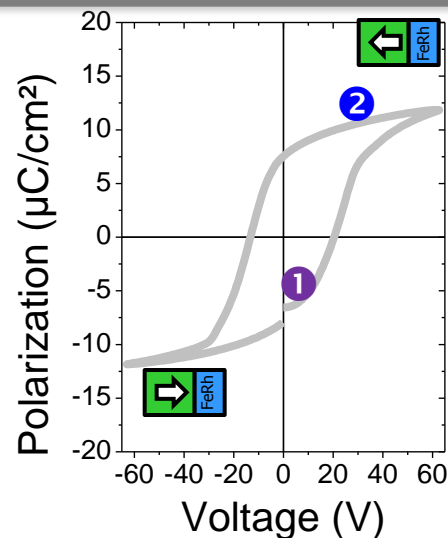


- ⊙ Transition is first order
- ⊙ Jump of cell volume at  $T^*$

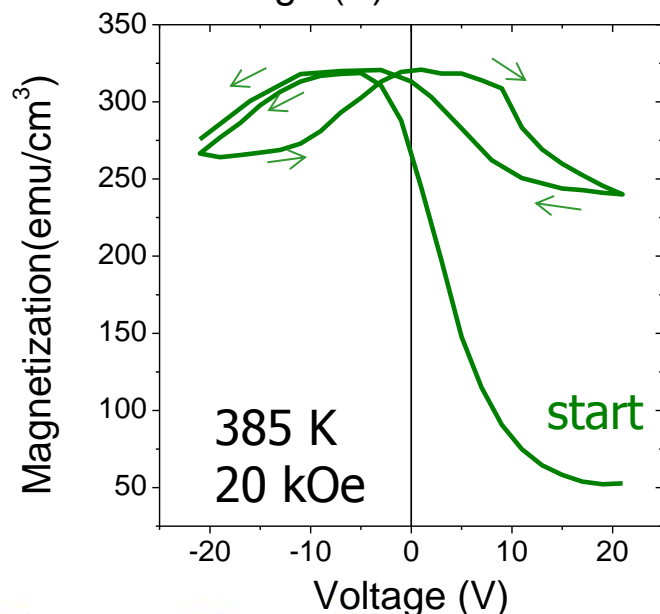
**Goal** : drive AF to FM transition by electric field

➔ Grow FeRh on BaTiO<sub>3</sub> crystals  
(ferroelectric & ferroelastic)

- ⊙ At 0 V, coexistence of a and c domains
- ⊙ Applied voltage : increase of c domain fraction (up to ~100%)
- ⊙ Compressive strain applied to FeRh



- At 0V at 20 kOe,  $T^* \approx 360$  K
- Voltage shifts  $T^*$  by  $\sim 20$  K



- Huge voltage induced magnetization change
- First branch : largest effect (1st order transition)
- Then, hysteretic, reversible magnetoelectric effect
- Effect roughly symmetric
- ➔ Mainly driven by strain
- Supported by first principles calculations

Nature Materials 13, 345 (2014)



# Conclusion

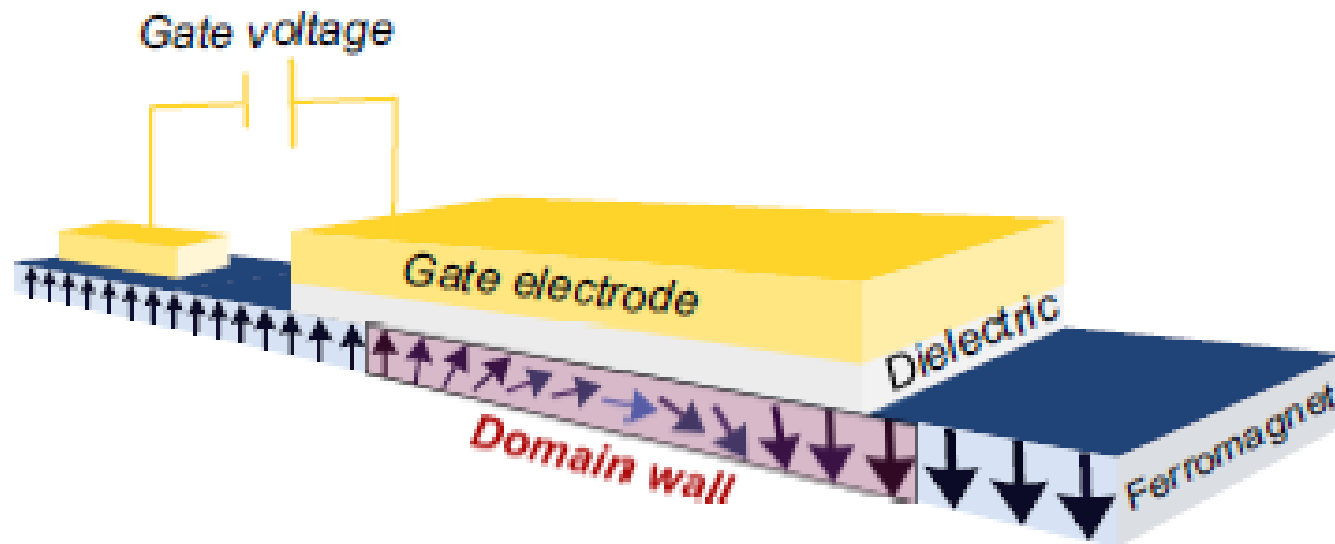
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- Proof of concepts of electric field effect have been realized using innovative approaches
- 4 meetings of Axe 2 have been organized
- 1 Japanese-French workshop has been organised
- Call for 3 postdocs to further investigate the best approaches for low power spintronics



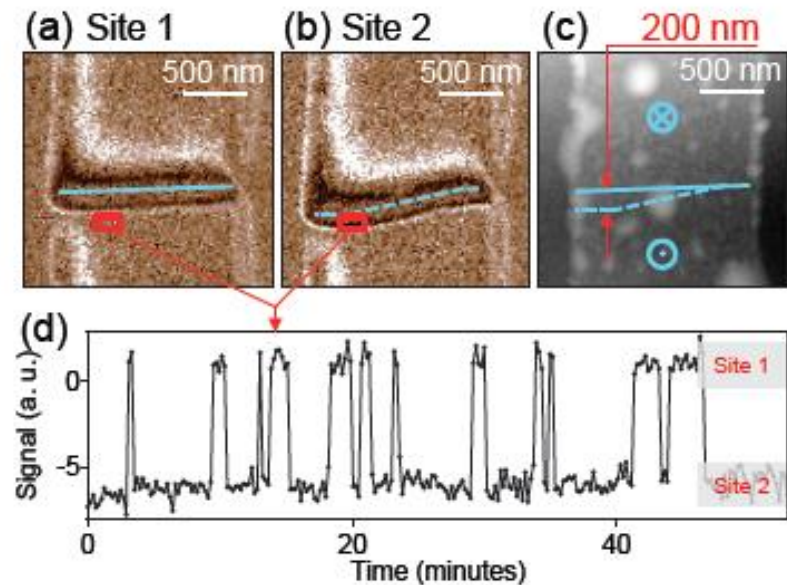
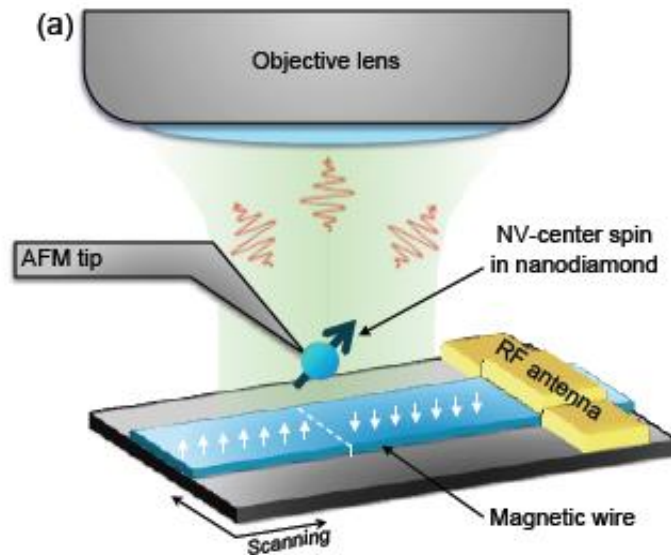
# Domain wall motion in nanodevices

Combine polarized current and electric field effect to assist DW motion in nanowires (propagation, nucleation, depinning)



# Domain wall motion in nanodevices

Observe DW structure under electric field using NV center microscopy



J.P.Tetienne, T.Hingant, J.F roch,  
V.Jacques, ENS CACHAN

**CVS**  
C A C H A N

**LPS**  
ORSAY



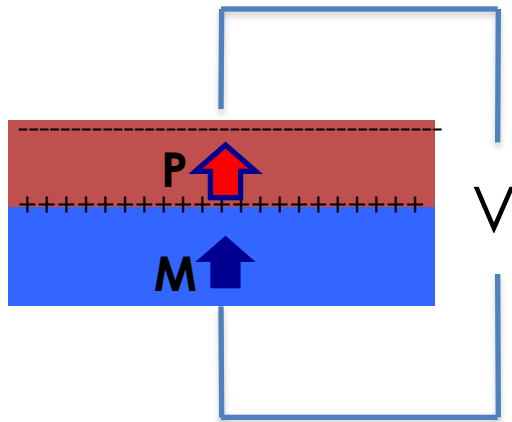
J.P.Tetienne et al, Science 2014

**NanoSaclay**  
Laboratoire d'Excellence  
en Nanosciences et Nanotechnologies

Toward ultra low power spintronics devices

# Artificial multiferroics

- Drive AF to FM transition in a non-volatile way
- Dope FeRh with different elements to tune  $T^*$  to be at 300K
- Extend approach to other systems



## Oxide electronics :

- Induce multiferroicity in oxides through strain and interface engineering
- Explore new approaches for magnetoelectric coupling

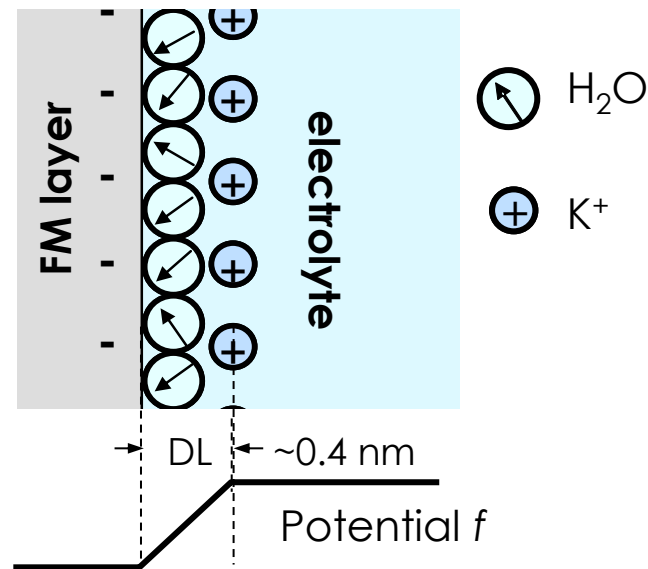
# Electrochemical approach

## Running collaboration IEF – PMC:

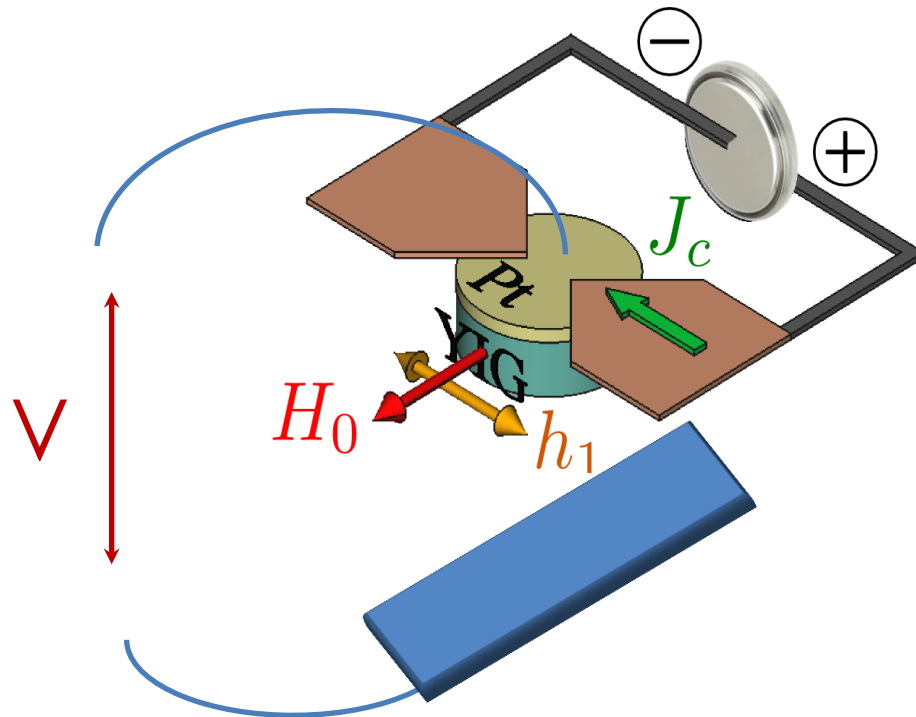
- Control of anisotropy via light induced charge transfer between Adsorbed photochromes and a ferromagnetic ultrathin layer

## Future collaboration IEF – LPS - PMC:

- In situ MOKE microscopy to investigate the influence of E-field on the DMI in asymmetric systems Au/cobalt/solution.



# Electric field control of FMR



-FMR in YIG/Pt measured by MRFM  
-FMR is particularly sensitive to any change in damping and anisotropy

- A current flowing in the Pt will generate a spin current by Spin Hall effect. Spins will accumulate at the interface and affect the YIG surface anisotropy.
- A voltage will be applied between top and bottom electrodes of the insulating YIG. The internal electric field generated should affect the ferromagnetic anisotropy